

Notice of References Cited

Application/Control No.

10/071,456

Applicant(s)/Patent Under
Reexamination
DICKERSON ET AL.

Examiner

Anh D. Mai

Art Unit

2814

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U.S. PATENT DOCUMENTS				Name	Classification
*		Document Number Country Code-Number-Kind Code	Date MM-YYYY		
	A	US-			
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NON-PATENT DOCUMENTS			Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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